

AMENDMENTS TO THE SPECIFICATION

Please amend paragraph [0030] with the following amended paragraph:

[0030] In FIG. 7, an example of axial temperature distribution in the vicinity of the seed crystal is shown. Conventionally achieved axial temperature distribution is the axial temperature distribution 15. As shown in [[a]] an axial temperature distribution [[18]] 35, the portion where the seed crystal 14 is placed is locally cooled to make only the temperature gradient in the vicinity of the seed crystal 14 to 50° C/cm and the other furnace a temperature gradient is made to 5° C/cm. As a result, the seeding process is performed under an optimal temperature condition for crystal growth on the solid-liquid interface by retaining only the temperature gradient of the seed crystal 14 the same as that of the conventional temperature distribution 15.

Please amend paragraph [0039] with the following amended paragraph:

[0039] In FIG. 8, an example of axial temperature distribution in the vicinity of the seed crystal is shown. Conventionally achieved axial temperature distribution is the axial temperature distribution 15. As shown in the axial temperature distribution [[18]] 35, the portion where the seed crystal 14 is placed is locally cooled to make the temperature gradient in the vicinity of the seed crystal 14 to 50° C/cm at the lower portion, 25° C/cm at the upper portion, and the other furnace temperature gradient is made to 5° C/cm. As a result, the seeding process is performed under an optimal temperature condition for crystal growth on the solid-liquid interface by retaining only the temperature gradient of the lower portion of the seed crystal 14 the same as that of the conventional temperature distribution 15